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(54) Title: WET PROCESSING WITH AUTOMATIC PROCESS CONTROL

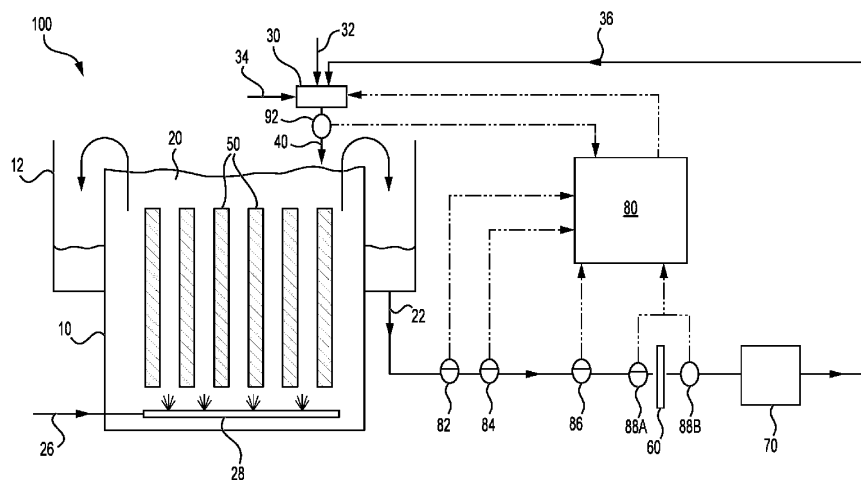


FIG. 1

(57) Abstract: A system and a method of wet processing includes receiving real-time signals indicative of one or more of a pH, a temperature, and an electrical conductivity of a liquid chemical in a wet processing tank, and determining values of one or more of a composition, a flow rate, and the temperature of the liquid chemical that will improve or maintain an etch rate of the liquid chemical in the wet processing tank. One or more of the composition, the flow rate, and the temperature of the liquid chemical in the wet processing tank may then be adjusted to the determined values.

[Continued on next page]

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